

Multimillion-atom molecular dynamics simulation of atomic level stresses in Si(111)/Si₃N₄(0001) nanopixels

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(Received 22 December 1997; accepted for publication 18 February 1998)

Ten million atom multiresolution molecular-dynamics simulations are performed on parallel computers to determine atomic-level stress distributions in a 54 nm nanopixel on a 0.1 μm silicon substrate. Effects of surfaces, edges, and lattice mismatch at the Si(111)/Si₃N₄(0001) interface on the stress distributions are investigated. Stresses are found to be highly inhomogeneous in the nanopixel. The top surface of silicon nitride has a compressive stress of +3 GPa and the stress is tensile, -1 GPa, in silicon below the interface. © 1998 American Institute of Physics. [S0003-6951(98)00116-8]

Sub-100 nm pixel sizes pose special challenges in Si electronics. In this regime, the significance of spatial inhomogeneities in the dopant distribution to the device characteristics is being increasingly appreciated.¹ Spatially nonuniform stresses induced by such nanoscale pixellation may have profound impact²—rapidly varying stresses at and near edges may lead to defect formation or even initiate a crack. Understanding the stress distribution is therefore essential in the design of nanoscale devices.

On larger (>1 μm) length scales, edge stresses in Si/SiO₂ and Si/Si₃N₄ have been examined utilizing the framework of linear elasticity and finite-element (FE) simulations.^{3,4} In nanoscale devices, however, the surface-to-volume ratio is so large that the influence of surfaces, edges, and corners on elastic properties become significant. In addition, chemical bonding at the Si/Si₃N₄ interface introduces types of stresses not present in silicon or silicon nitride materials. These effects have to be included in constitutive relations to achieve realistic description of nanoscale devices in the FE approach. An alternative approach is to use molecular-dynamics (MD) simulations where surface and interface bonding effects are explicitly included at the atomistic level. With recent progress in parallel computer architectures, it has now become possible to carry out direct atomistic simulations for submicron structures with realistic descriptions of the materials involved. In particular, large-scale MD simulations have proven to be useful in the study of dynamic fracture.⁵ MD simulations provide spatially resolved stress distributions on the length scales not accessible to experimental techniques, such as MicroRaman

spectroscopy.⁶ Such numerical experiments can be used to establish the validity of constitutive relations used in FE simulations, in particular the treatment of surface/interface/edge effects.

In this letter, the results of a ten million atom molecular-dynamics study of atomic stress distribution in a Si/Si₃N₄ nanopixel are reported. The simulations were performed on 128 processors of the 256-processor HP Exemplar at Caltech requiring a total of 180 h of computational time. We have considered a crystalline Si₃N₄ film forming a coherent Si(111)/Si₃N₄(0001) interface⁷ with the Si mesa. An interatomic potential model for the Si/Si₃N₄ interface has been developed using the charge transfer values computed from a self-consistent linear combination of atomic orbitals (LCAO) electronic structure calculation.^{8,9} The calculated stress distributions illustrate the role of various surface effects and the 1.1% lattice mismatch between Si(111) and Si₃N₄(0001) surfaces.

A variety of empirical interatomic potentials for atomistic modeling of silicon have been developed over the years.¹⁰⁻¹⁴ For our purposes, we have chosen the well-known Stillinger-Weber potential,¹² which provides a satisfactory description of bulk crystalline silicon. Bulk Si₃N₄ is modeled using a combination of two- and three-body interactions which include charge transfer, electronic polarizability, and covalent bonding effects.¹⁵ This potential provides a good description of the structural and mechanical properties and dynamical behavior¹⁶ (static structure factor, bulk and Young's moduli, and phonon density of states) and fracture behavior of crystalline and amorphous Si₃N₄.¹⁷ To describe the bonding across the Si/Si₃N₄ interface, the interface atoms are treated differently from those in the bulk. LCAO elec-

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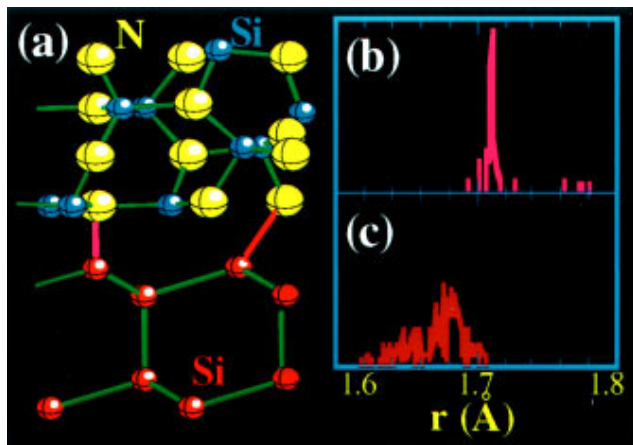


FIG. 1. (a) Si(111)/Si₃N₄(0001) interface. (b) and (c) Si–N bond length distribution for two different bonds marked in magenta and red in (a).

tronic structure calculations⁸ provide a guide in determining the charge transfer across the interface.

The Si(111)/Si₃N₄(0001) interface structure is characterized by calculating bond-length and bond-angle distributions. Figure 1(a) shows a schematic view of the interface. Si atoms on the Si(111) surface form bonds with N atoms in Si₃N₄. There are two different types of such bonds (shown in magenta and red, respectively). The bond-length distributions for the two types of bonds across the interface and in bulk Si₃N₄ are shown in Figs. 1(b) and 1(c). The Si–N bond length across the interface is close to that in bulk Si₃N₄ (1.73 Å).

The main issue we address in these simulations is the local stress distribution in Si(111)/Si₃N₄(0001) nanopixels. An efficient algorithm for parallel architectures has been developed to handle multimillion-atom molecular dynamics simulations for the Si/Si₃N₄ system. Additional computational speedup is achieved by using a multiple-time step approach¹⁸ to exploit the separation of time scales and Langevin dynamics approach to reduce the length of equilibration runs for inhomogeneous systems.

The simulated system consists of a 540 Å × 327 Å × 133 Å Si mesa on top of a 1077 Å × 653 Å × 230 Å Si(111) substrate. Periodic boundary conditions are used in the plane of the substrate. The top surface of the mesa is covered with a 83-Å-thick α -crystalline Si₃N₄(0001) film. The lattice Si(111)/Si₃N₄(0001) interface involves a 1.1% lattice mismatch (2×2 unit cell of Si is slightly smaller than one unit cell of Si₃N₄). We have also considered a scenario where the parameters of the Si potential are modified so that the lattice constants of Si and Si₃N₄ match exactly. This procedure allows us to isolate the effect of the lattice mismatch on the interfacial stress distribution.

Preparation of the nanopixel is done as follows. First, the Si system and a Si₃N₄ film are separately relaxed to a zero-force configuration using the steepest-descent approach and placed at a distance of 6 Å from each other. The separation distance is then reduced to 1.5 Å in steps of 0.5 Å. At each step, the system is quenched to zero temperature. Subsequently, the system is heated and thermalized at 300 K using the Langevin dynamics.

Atomistic-level stresses are calculated for the two cases of mesas without and with lattice mismatch. The stresses in

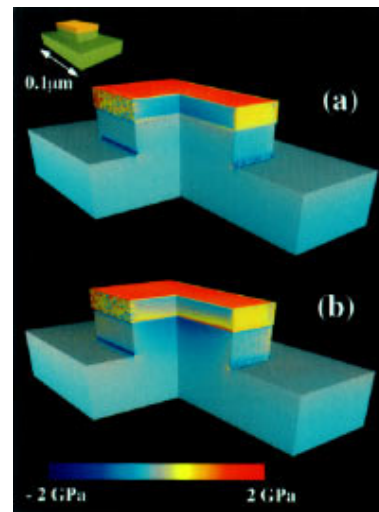


FIG. 2. Stress distribution in a Si/Si₃N₄ nanopixel, (a) without lattice mismatch and (b) in the presence of the 1.1% lattice mismatch. To show the stresses inside the nanopixel one quarter of the system is removed and the value of the hydrostatic stress is color coded.

Si and Si₃N₄ are averaged over the appropriate unit cells, which is necessary to obtain meaningful stress distributions in the case of binary systems such as Si₃N₄ which have atoms of widely different sizes.

Figure 2(a) shows the spatially resolved stress in the absence of the lattice mismatch. Here the stresses are primarily due to the surface effects. In addition, the stress distribution contains stress singularities near the edges of the mesa/substrate boundary. The 1.1% Si/Si₃N₄ lattice mismatch introduces additional contributions to the stress at the interface: compressive stress in Si₃N₄ facing tensile stress in Si [see Fig. 2(b)]. The mismatch-induced stress penetrates deep into the Si mesa to form a tensile stress well.

The hydrostatic $[(\sigma_{xx} + \sigma_{yy} + \sigma_{zz})/3]$ and in-plane $[(\sigma_{xx} + \sigma_{yy})/2]$ stresses along the z axis through the center of the nanopixel are plotted in Fig. 3. The background color corresponds to the color map used in Fig. 2. The stress in the absence of the lattice mismatch is shown in Fig. 3(a). The top surface of the Si₃N₄ film is subject to a strong compressive

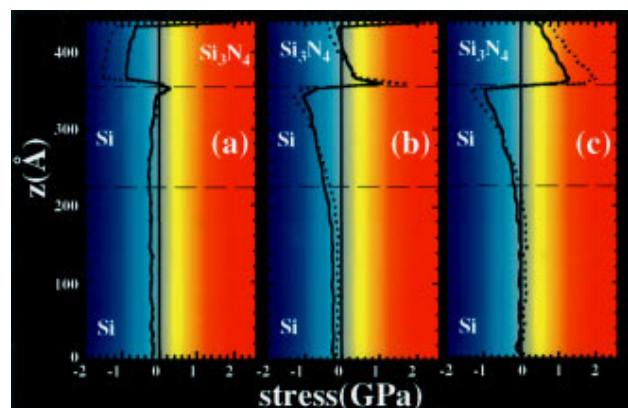


FIG. 3. Hydrostatic $[(\sigma_{xx} + \sigma_{yy} + \sigma_{zz})/3]$ (solid curve) and in-plane $[(\sigma_{xx} + \sigma_{yy})/2]$ (dashed curve) stresses along the z axis through the center of the nanopixel. The background color corresponds to the color map used to show stresses in Fig. 2. (a) lattice matched Si(111)/Si₃N₄(0001) interface, (b) lattice mismatched Si(111)/Si₃N₄(0001) interface, and (c) difference of lattice matched and mismatched interfaces.

sive stress due to repulsive forces between the N atoms on the surface. Additional stress contributions arise due to intrinsic stress at the interface. As a result, the interior of the Si₃N₄ film experiences tensile stress. The lattice mismatch results in an additional compressive stress in Si₃N₄ above the interface and tensile stress in Si [see Fig. 3(b)]. To isolate the effect of the lattice mismatch, we subtract the stress in the lattice matched system [Fig. 3(a)] from the lattice mismatched data of Fig. 3(b). The resulting stress contribution entirely due to the lattice mismatch is shown in Fig. 3(c). The magnitude and spatial variation of this mismatch-induced stress is consistent with linear elasticity estimates and finite element calculations.⁴

In conclusion, ten million atom molecular dynamics simulations using the space-time multiresolution algorithms have been performed on parallel computers to investigate the stress distribution in a Si(111)/Si₃N₄(0001) mesa on Si(111) substrate. Stress concentration is observed near the interface and at the mesa/substrate edges. A lattice mismatch of 1.1% at the Si(111)/Si₃N₄(0001) interface manifests as a stress well in the center of the mesa. Additional simulations are currently under way to study different geometries of the nanopixel and the effect of amorphous Si₃N₄ in place of crystalline silicon nitride.

Work supported by the Austrian FWF (J01146-PHY and J01444-PHY), DOE (Grant No. DE-FG05-92ER45477), NSF (Grant No. DMR-9412965), AFOSR (Grant No. F 49620-94-1-0444), USC-LSU MURI (Grant No. F 49620-95-1-0452), ARO (Grant No. DAAH04-96-1-0393), and PRF (Grant No. 31659-AC9). Simulations involving one to two million atoms were performed on the parallel machines in the Concurrent Computing Laboratory for Materials Simulations at LSU. The ten million atom simulations were car-

ried out at the 256-processor HP Exemplar at Caltech. Access to the Exemplar was provided by the National Partnership for Advanced Computational Infrastructure (NPACI) through a cooperative agreement from the National Science Foundation.

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